

Supplementary information:

## Highly Stretchable Strain Sensor Based on Electrospun Carbon Nanofibers for Human Motion Monitoring

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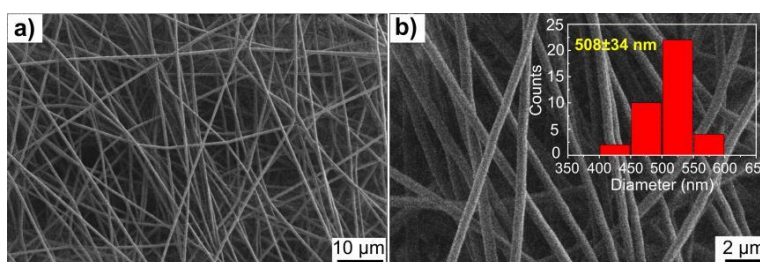


Fig. S1 SEM images of the electrospun PAN nanofibers.

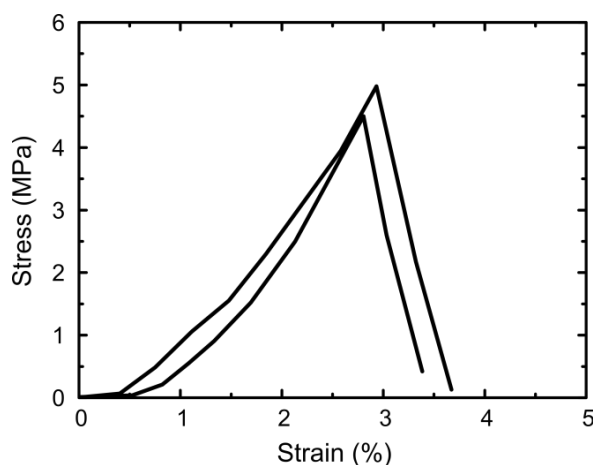
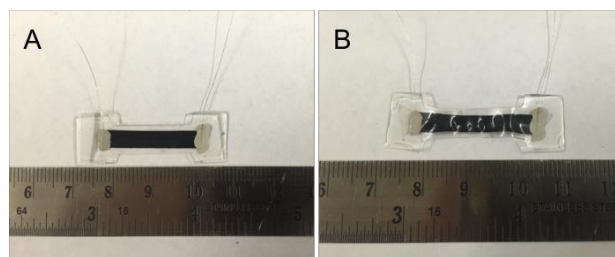


Fig.S2 Stress-strain curves of CNFs mat.



**Fig.S3** Optical images of strain sensor when unstretched (A) and after stretched for 350% strain (B).

**Table.S1.** Comparison of the performance of strain sensors in this work and in other reported works. The references are selected based on the materials and/or processes for strain sensors reported in recent years.

Materials	Prepare/assembly method	Stretchability	Gauge factor	Cycles	Reference
Ag nanoparticles	transfer ink patterning	20%	2.05	1000	1
Ag nanowires	drop casting	70%	2-14	-	2
PANI/Au nanowire	Chinese penbrush writing	100%	13	10000	3
Si nanowires	vapor-liquid-solid process	50%	350	~500	4
Carbon nanotubes	dry-spun	900%	64	10000	5
	layer-by-layer drop casting	100%	62.7	1000	6
	drop at surface	530%	12-25	1000	7
graphene	soaking	800%	35	1000	8
	layer-by-layer assembly	150%	-	-	9
	embedding	100%	7.1	-	10
<b>Electrospun carbon nanofibers</b>	<b>Electrospinning &amp; sandwiching</b>	<b>300%</b>	<b>72</b>	<b>8000</b>	<b>This work</b>

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